

Title (en)
APPARATUS FOR LASER ANNEALING OF LARGE SUBSTRATES AND METHOD FOR LASER ANNEALING OF LARGE SUBSTRATES

Title (de)
VORRICHTUNG ZUM LASERAUSGLÜHEN GROSSER SUBSTRATE UND VERFAHREN ZUM LASERAUSGLÜHEN GROSSER SUBSTRATE

Title (fr)
APPAREIL ET PROCÉDÉ DE RECUIT AU LASER DE GRANDS SUBSTRATS

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Application
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Abstract (en)
[origin: WO2007122061A1] The invention relates to an apparatus for laser annealing of large substrates comprising an optical device for generating a narrow illuminating line (31) on an illumination plane (36) of said substrate (32), said illumination line (31) being generated from a laser beam and having a cross-section with an expansion in a first direction and an expansion in a second direction, whereby said expansion in said first direction exceeds said expansion in said second direction by a multiple, and a scanning device being constructed for scanning a first section of said illumination plane of said substrate with said illuminating line in said second direction. According to the invention the apparatus comprises a rotating device for rotating (39) said substrate (32) relative to said illuminating line (31) by 180° about an axis (38) of rotation being normal to said illumination plane (36) after scanning said first section (37), whereby said scanning device is constructed for scanning a second section of said illumination plane (36) of said substrate (32) being adjacent to said first section of said illumination plane (36) of said substrate (32) with said illuminating line (31) in said second direction (y).

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